All Times are local time in Berkeley, CA, USA (PDT)  On June 2, 2024 Short Courses is on-line only. June 3 Short Course is in a Hybrid format. From June 4-6, 2024 workshop is in-person only.  Version: April 16, 2024. For questions or comments please contact info@euvlitho.com  Short Course  8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only)  All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event.  Short Course: EUV and Soft X-Ray Sources  Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich  EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in  Physics of EUV and Short Wavelength  Gerry O'Sullivan  UCD  Sources with Focus on Atomic Physics  Break  0:15 10:15 AM 10:30 AM Province on Atomic Physics  UC Berkeley  UC Berkeley  UN Multilayers  Univ of Colorado and Henry C. Kapteyn  K&M Labs  High Harmonic EUV Sources								
On June 2, 2024 Short Courses is on-line only. June 3 Short Course is in a Hybrid format. From June 4-6, 2024 workshop is in-person only.  Version: April 16, 2024. For questions or comments please contact info@euvlitho.com  Short Course  8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only)  All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event.  Short Course: EUV and Soft X-Ray Sources  Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich  EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in Physics of EUV and Short Wavelength Gerry O'Sullivan UCD Sources with Focus on Atomic Physics Break UCS Berkeley UC Berkeley Univ of Colorado and Henry C. Kapteyn Henry C. Kapteyn K&M Labs Break UT Austin and Tau Systems UT Austin and Tau Systems AN Test and Speaker Check-in 1:30 10:30 AM 12:30 PM 12:30 PM 12:30 PM 12:30 PM 13:30 SM 12:00 PM 12:30 PM 13:34 SPM 13:34 SPM 13:34 SPM 13:35 SPM 13:3	# Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
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8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only)  All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event.  Short Course: EUV and Soft X-Ray Sources  Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich  EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in  Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics  Break  UCD Berkeley  UCD Berkeley  Univ of Colorado and Henry C. Kapteyn  Henry C. Kapteyn  Break  UT Austin and Bjorn Manuel Hegelich  Tau Systems  UT Austin and Tau Systems  AND Test and Speaker Check-in Distructors: 8:30 AM 8:45 AM 1:30 8:45 AM 10:15 AM 10:15 AM 10:30 AM 12:00 PM 1:30 10:30 AM 12:00 PM 1:30 12:30 PM 2:00 PM 2:15 PM 3:45 PM and X-ray Sources		Ve	ersion: April 16, 2024. For	questions or co	mments please contact info@euvlitho.com			
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Short Course: EUV and Soft X-Ray Sources  Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich  EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in Physics of EUV and Short Wavelength Gerry O'Sullivan UCD Sources with Focus on Atomic Physics Break  UC Berkeley UC Berkeley Univ of Colorado and Henry C. Kapteyn  UT Austin and Bjorn Manuel Hegelich  Break  UT Austin and Laser-driven accelerators and coherent EUV 1:30 2:15 PM 3:45 PM 3:45 PM 3:45 PM 1:30 10:30 AM 12:00 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 PM 3:45 PM		8:30 AM, S	unday, June 2, 2	2024, Berk	eley, CA (Course is held onl	ine On	ly)	
Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich  EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in  Gerry O'Sullivan  UCD  Sources with Focus on Atomic Physics  Break  1:30  10:15 AM 10:30 AM 12:00 PM  Marcelo Ackerman  UC Berkeley  Lunch Break  0:30  1:30  12:30 PM 12:30 PM  Lunch Break  0:15  1:30  12:30 PM 12:30 PM  Lunch Break  0:15  1:30  12:30 PM 12:30 PM  Lunch Break  Univ of  Colorado and Henry C. Kapteyn  K&M Labs  Break  0:15  1:30  12:30 PM 12:30 PM  Laser-driven accelerators and coherent EUV  1:30  2:15 PM  3:45 PM  3:45 PM  AND TEST AND TO SET	All Tin	nes are for Berke	eley, CA, USA. Ple	ase estimat	te times for your own time zone	es. It is	a live ev	ent.
EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information.  AV Test and Speaker Check-in  Gerry O'Sullivan  UCD  Sources with Focus on Atomic Physics  Break  UC Berkeley  UC Berkeley  Univ of Colorado and Henry C. Kapteyn  WA Labs  UT Austin and Bjorn Manuel Hegelich  UCD  AV Test and Speaker Check-in  O:15 8:30 AM 8:45 AM 10:15 AM 10:30 AM 10:30 AM 10:30 AM 10:30 AM 12:00 PM 1:30 12:30 PM 1:30 12:30 PM 2:00 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 AM 10:15 AM 10:15 AM 10:30 AM 12:00 PM 1:30 12:30 PM 2:00 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 AM 10:15 AM 10:15 AM 10:15 AM 10:15 AM 10:30 AM 12:00 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 AM 10:15 AM 10:15 AM 10:15 AM 10:30 AM 12:00 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 PM			Short Course	e: EUV ar	nd Soft X-Ray Sources			
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Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics  Break  UC Berkeley UC Berkeley Univ of Colorado and Henry C. Kapteyn  Bjorn Manuel Hegelich  UCD Break UCD Break  UCD Break  UC Berkeley EUV Multilayers  Lunch Break  Univ of Colorado and K&M Labs Break UT Austin and Tau Systems  Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics  1:30 10:15 AM 10:10 A	EU	VL Short Courses a	nd EUVL Workshop re	equire separate	e registrations. Please visit www.euvlitho	o.com for	informatio	n.
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Marcelo Ackerman  UC Berkeley  Lunch Break  Univ of Colorado and K&M Labs  Henry C. Kapteyn  Break  UT Austin and Bjorn Manuel Hegelich  UC Berkeley  EUV Multilayers  Lunch Break  Univ of Colorado and K&M Labs  Fundamentals and Applications of Coherent High Harmonic EUV Sources  Break  UT Austin and Tau Systems  UT Austin and Tau Systems  EUV Multilayers  Univ of Colorado  Euror Break  UT Austin and Tau Systems  EUV Multilayers  1:30 12:30 PM 2:00 PM 2:15 PM 3:45 PM 3:45 PM					Break			
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Univ of Colorado and Henry C. Kapteyn  Break  UT Austin and Bjorn Manuel Hegelich  Univ of Colorado and K&M Labs  High Harmonic EUV Sources  Break  UT Austin and Tau Systems  UT Austin and Applications of Coherent High Harmonic EUV Sources  Break  UT Austin and Tau Systems  Tau Systems  1:30 12:30 PM 2:00 PM 2:15 PM 3:45 PM 3:45 PM			Marcelo Ackerman	UC Berkeley	-			
Colorado and Henry C. Kapteyn  K&M Labs  Break  UT Austin and Tau Systems  Bjorn Manuel Hegelich  Colorado and K&M Labs  Fundamentals and Applications of Coherent High Harmonic EUV Sources  Break  UT Austin and Laser-driven accelerators and coherent EUV and X-ray Sources  1:30 2:15 PM 3:45 PM					Lunch Break			
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Bjorn Manuel Hegelich Tau Systems and X-ray Sources						0:15	2:00 PM	2:15 PM
				UT Austin and	Laser-driven accelerators and coherent EUV	1:30	2:15 PM	3:45 PM
Short Course Adjourned			Bjorn Manuel Hegelich	Tau Systems	and X-ray Sources			
Short Course Adiourned								
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# Paper #	Area	Presenter	Company	Title	Duration	Start	Finish					
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			Short (	Course								
0.20 44	Monday lung 2	2024 Parkalay CA	011011		vill bo in	norcon c	+ I DI \					
6.30 AIV	i, ivioliday, Julie 3,		•	eld in hybrid mode. All instructors v	viii be iii	-person a	IL LDL J					
		Short C	Course: E	UV Lithography								
Instructo	ors: Vivek Bakshi (E	EUV Litho, Inc.), Patr	ick Naulleau	(CXRO), Sangsul Lee (Postiche Univ	ersity),		and					
	Jan van Shoot (ASML)											
EU	VL Short Courses a	nd EUVL Workshop re	equire separat	e registrations. Please visit www.euvlith	o.com for	informatio	n.					
				AV Test and Speaker Check-in	0:15							
					1:30	8:45 AM	10:15 AM					
		Vivek Bakshi	EUV Litho Inc.	Lecture								
		VIVER BURSTII	LOV LITTIO IIIC.	Break	0:15	10:15 AM	10·30 AM					
						10:30 AM						
			POSTECH and									
		Sangsul Lee	PAL	Lecture								
				Lunch Break	1:00	12:00 PM	1:00 PM					
					1:30	1:00 PM	2:30 PM					
		Patrick Naulleau	EUV Tech	Lecture								
				Break	0:15	2:30 PM	2:45 PM					
					1:30	2:45 PM	4:15 PM					
		Jan van Schoot	ASML	Lecture								
			Short Course	e Adjourned								



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
		20	24 EUVL Wor	kshop	and Supplier Showca	se		
	Pleas	e see Abstract Bo	ok on website www.	euvlitho.com	n for abstracts and co-author(s) info	rmation	by pape	r #.
	12	2:00 PM, Tuesday	, June 4, 2024, LBL, CA	(Workshop	held in-person only, Meeting room	to be ar	nounced	d)
		S	essions 1 - 2: LB	SL and Su	ipplier Program Showcas	е		
		Se	ession 1: LBL Program Show	case; Session C	hair: Ricardo Ruiz and Bruno La Fontaine (LBL	)		
					AV Test, Speaker Check-in and Registration	0:30	12:00 PM	12:30 PM
1		Introduction	Vivek Bakshi / Patrick Naulleau	EUV Litho /	Welcome and Announcements	0:10	12:30 PM	12:40 PM
1	P7	Keynote	John Shalf	LBL	Computing Beyond Moore's Law	0:30	12:40 PM	1:10 PM
1	P106	LBL Showcase	Ricardo Ruiz	LBL	A Holistic Approach to Patterning Science at Berkeley Lab	0:15	1:10 PM	1:25 PM
1	P102	LBL Showcase	Maurice Garcia-Sciveres	LBL	Nanoscale Photon Sensing	0:15	1:25 PM	1:40 PM
1	P105	LBL Showcase	Paul Ashby	LBL	Spatially Resolved EUV Resist Dissolution	0:15	1:40 PM	1:55 PM
1	P103	LBL Showcase	Cheng Wang	LBL	Characterization of Chemical/structural Information of Latent Image via Critical- dimension Resonant Soft X-ray Scattering	0:15	1:55 PM	2:10 PM



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
						0:15	2:10 PM	2:25 PM
1	P101	LBL Showcase	Adam Schwartzberg	LBL	2024 LBL Program Showcase Presentation			
					Multimodal characterization of electrons	0:15	2:25 PM	2:40 PM
					and excitons in 2D materials and their			
1	P107	LBL Showcase	Archana Raja	LBL	heterostructures			
						0:30	2:40 PM	3:10 PM
					Coffee Break			
			Session 2: Supplier Progra	m Showcase; Se	ession Chair: Vivek Bakshi (EUV Litho, Inc.)			
						0:15	3:10 PM	3:25 PM
2	P81	Supplier Showcase	Richard Ciesielski	PTB	Synchrotron-based EUV metrology at PTB			
						0:15	3:25 PM	3:40 PM
			Jacqueline van		TNO EUV Materials Research for EUV			
2	P85	Supplier Showcase	Veldhoven	TNO	Infrastructure			
						0:15	3:40 PM	3:55 PM
2	P88	Supplier Showcase	Bruno La Fontaine	LBL	EUVL Capabilities at CXRO			
						0:15	3:55 PM	4:10 PM
					Coffee Break			
						1:30	4:10 PM	5:40 PM
			All		LBL Facility Tour (Location TBA)			
		1	, 	Workshop Adjou	urned for the Day	+		



# Paper	# Area	Presenter	Company	Title	Duration	Start	Finish
	8:30 AM, W	ednesday, June 5, 2	024, LBL, Be	erkeley, CA (Workshop held in-ر	person	only)	
		Session 3: Keynote	Presentation	s; Session 4: Supplier Showcase,			
	Sessi	ion 5-6: Resist and Patt	erning 1 & 2;	<b>Session 7: Poster Session and Rece</b>	ption		
		Session 3: Keyno	ote - 1; Session Ch	nair: Patrick Naulleau (EUV Tech)			
				Breakfast	0:30	8:00 AM	8:30 AM
					0:30	8:30 AM	9:00 AM
				AV Test, Speaker Check-in and Registration			
					0:10	9:00 AM	9:10 AM
	Introduction	ТВА	LBL	Welcome to LBL			
					0:10	9:10 AM	9:20 AM
	Introduction	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements			
					0:30	9:20 AM	9:50 AM
3 P4	Keynote	Steven Carson	Intel	High-NA EUV: An Update on Introduction			
					0:30	9:50 AM	10:20 AM
3 P5	Keynote	Steve Snyder	Micron	Full Lifetime EUV Cost vs Performance for DRAM			
					0:30	10:20 AM	10:50 AM
2 04	Voyanto	la Vana Kana	Samsuna	New development of EUV materials and MI			
3 P1	Keynote	In-Yong Kang	Samsung	solutions for High NA mask  Coffee Break	0.20	10:50 AM	11.10 484
				Collect Dicar	0.20	TO'SO HIM	TT.TO AIVI



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
			Session 4:	Supplier Showca	se; Session Co-Chairs: TBA			
					Veeco Ion Beam Deposition Advancement	0:15	11:10 AM	11:25 AM
					and Diamond Like Carbon as Novel Material			
4	P86	Supplier Showcase	Meng Lee	Veeco	for EUV Mask Blanks (Invited)			
					Distance from Design with High Landing	0:15	11:25 AM	11:40 AM
					Energy SEM Imaging on Advanced Logic			
4	P87	Supplier Showcase	Michael Shifrin	AMAT	Devices (Invited)			
					Preparing the Availability of EUV Light	0:15	11:40 AM	11:55 AM
					Sources for High Volume Manufacturing			
4	P83	Supplier Showcase	Henry Chou	Energetiq	(Invited)			
						0:15	11:55 AM	12:10 PM
4	P82	Supplier Showcase	Matt Hettermann	EUV Tech	Applications of EUV Metrology Tools			
						0:15	12:10 PM	12:25 PM
					Nanoscale Chemical Analysis of EUV Resists			
4	P84	Supplier Showcase	Tom Albrecht	Molecular Vista	(Invited)			
					Lunch	1:05	12:25 PM	1:30 PM



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
			Session 5: Res	sist and Patterni	ng- 1; Session Co-Chairs: TBA			
						0:15	1:30 PM	1:45 PM
		Resist and Patterning -			Dry Resist Patterning Readiness Towards			
5	P51	1	Anuja De Silva	LAM	High NA EUV Lithography (Invited)			
						0:15	1:45 PM	2:00 PM
		Resist and Patterning -			Advanced Processes for High-NA EUV			
5	P53	1	Congque Dinh	TEL	Lithography (Invited)			
						0:15	2:00 PM	2:15 PM
		Resist and Patterning -			Multi-Trigger Resist Patterning towards			
5	P55	1	Alex Robinson	IM	High–NA EUV Lithography (Invited)			
					Enhancement of Photosensitivity and	0:15	2:15 PM	2:30 PM
		Resist and Patterning -		Sungkyunkwan	Stability of Sn-12 EUV Resist by Integrating			
5	P56	1	Myung-Gil Kim	University	Photoactive Nitrate Anion			
						0:15	2:30 PM	2:45 PM
		Resist and Patterning -		John Hopkins	EUV Lithography Using Zeolitic Imidazolate			
5	P57	1	Michael Tsapatsis	University	Frameworks			
					DOE Accelerate Initiative Project for	0:15	2:45 PM	3:00 PM
		Resist and Patterning -		Brookhaven	Accelerating Next-Generation EUV			
5	P59	1	Chang-Yong Nam	National Lab	Photoresist Development (Invited)			
						0:15	3:00 PM	3:15 PM
		Resist and Patterning -		Hanyang	Hybrid Multilayer EUV Dry Resist for 1.5 nm			
5	P58	1	Myung Mo Sung	University	Technology Node			
					Coffee Break	0:20	3:15 PM	3:35 PM



Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
		Session 6: Res	sist and Pattern	ing - 2; Session Co-Chairs: TBA			
				Sequence Control in Polypeptoid	0:15	3:35 PM	3:50 PM
	Resist and Patterning -			Photoresists and Its Effects on Patterning			
P60	2	Chris Ober	Cornell	Performance (Invited)			
					0:15	3:50 PM	4:05 PM
	Resist and Patterning -			EUV CAR-NTD with New Developer for			
P67	2	Nishiki Fujimaki	Fuji Film	Chemical Stochastic Defect Reduction			
					0:15	4:05 PM	4:20 PM
	Resist and Patterning -			Probing Chemical Transformations in EUV			
P52	2	Oleg Kostko	CXRO	Resists			
				EUV Interference Lithography towards the	0:15	4:20 PM	4:35 PM
	Resist and Patterning -			Ultimate Resolution of Photon-based			
P54	2	lason Giannopoulos	PSI	Nanopatterning			
			Chonnam	Non-Alkyl Tin Oxo Cluster of CNU-TOC-	0:15	4:35 PM	4:50 PM
	Resist and Patterning -		National	01(4C-C) as Inorganic Resist for EUV			
P62	2	Hyun-Dam Jeong	University	Lithography			
				Evaluation of C-beam Generated EUV	0:15	4:50 PM	5:05 PM
	Resist and Patterning -		Kyung Hee	Lightning Source using Mirror and Filter			
P69	2	Umesh Balaso Apugade	University	Technique			
					0:15	5:05 PM	5:20 PM
	Resist and Patterning -			Performance of the Berkeley MET Using a			
P13	2	Ryan Miyakawa	CXRO	Stand-Alone Plasma Source			
				Break / Move to Poster Session Location	0:40	5:20 PM	6:00 PM
	P60 P67 P52 P62 P69	Resist and Patterning - 2 Resist and Patterning -	Resist and Patterning - 2  Resist and Patterning - 2	Resist and Patterning - 2 Chris Ober Cornell  Resist and Patterning - 2 Nishiki Fujimaki Fuji Film  Resist and Patterning - 2 Oleg Kostko CXRO  Resist and Patterning - 2 Iason Giannopoulos PSI  Resist and Patterning - 2 Hyun-Dam Jeong University  Resist and Patterning - 2 Umesh Balaso Apugade University  Resist and Patterning - 2 Umesh Balaso Apugade University	Session 6: Resist and Patterning - 2; Session Co-Chairs: TBA  Resist and Patterning - 2  Chris Ober Cornell Performance (Invited)  Resist and Patterning - 2  Resist and Patterning - 2	Session 6: Resist and Patterning - 2; Session Co-Chairs: TBA  Resist and Patterning - 2 Chris Ober Cornell Performance (Invited)  Resist and Patterning - 2 Chris Ober Cornell Performance (Invited)  Resist and Patterning - 2 Resist and Patterning - 2  Resist and Pa	Session 6: Resist and Patterning - 2; Session Co-Chairs: TBA  Resist and Patterning - 2  Resist and Patterning - 3  Resist and Patterning - 3  Resist and Patterning - 3  Resist and Patterning - 4  Resist and Patterning - 2  Resist and Patterning - 3  Resist and Patterning - 4  Resist and Pa



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
			S	Session 7: Poster Se	ssion and Reception			
						1:30	6:00 PM	7:30 PM
					Poster Session and Reception			
				Hanyang	Study of Enhancing Etching Performance of			
7	P20	Poster Session	Seungho Lee	University	Pt-based Absorber Material for EUV Mask			
					Experimental Investigation of the Mask			
				Hanyang	Diffraction Obstructed by the Critical-sized			
7	P21	Poster Session	Seungchan Moon	University	Sn Particles on EUV Pellicle			
					Energetiq Source Update: Spherically			
7	P39	Poster Session	Kosuke Saito	Energetiq	Shaped Source for High NA Metrology			
					Enhanced EUV Lighting with Focusing			
				Kyung Hee	Electrode Adapted C-beam Irradiation			
7	P41	Poster Session	Iksu Kim	University	Technique			
					Testing Platform of Extreme-ultraviolet			
7	P42	Poster Session	Wooram Kim	KRISS	(EUV) Materials and Optical Components			
					Taturah dan metatua merathi d			
				Chonnam	Tetrahydroxy-tetramethyl-			
					cyclotetrasiloxane as an Inorganic EUV			
7	P61	Doctor Cossian	livoung Dong	National	Resist: Exploring Cross-Linking Mechanisms			
/	P01	Poster Session	Jiyoung Bang	University	and Lithography Performance The Investigation of the Effect of Electron			
					Beam and Extreme Ultraviolet Irradiation			
				Chonnam	on Dibenzyltin Diacetate Thin Film Using			
				National				
7	P63	Poster Session	Hyook Vun	University	Local Analysis and Quantum Chemical Calculations			
/	F U 3	F U 3 LE 1 3 E 3 S 1 U 1 1	Hyeok Yun	Chonnam	Synthesis and Characterization of Novel			
				National	Two-in-One Type Siloxane Molecule			
7	P64	Poster Session	Wonchul Kee	University	Photoresist for EUV Lithography			
/	1 04	ו טאנפו שפאאוטוו	vvoliciiui kee	Offiversity	I Hotoresist for Lov Littlography			



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
					Enabling High-throughput Characterization			
					of Outgassing and Total Electron Yield for			
7	P65	Poster Session	Bernhard Lüttgenau	CXRO	Model EUV Resist Materials			
					Investigating Influence of Electron Affinity			
7	P66	Poster Session	Honggu Im	CXRO	on Electron Emission in EUV Photoresists			
				Hanyang	Dry Development Process for Vertically			
7	P68	Poster Session	Ji-Hoo Seok	University	Tailored Hybrid Multilayer EUV Photoresist			
			V	<b>Vorkshop Adjou</b>	rned for the Day			



# Pap	er# Area	Presenter	Company	Title	Duration	Start	Finish					
·	8:30 AM, Thu	rsday, June 6, 202	24, LBL, Ber	keley, CA (Workshop held i	n-pers	on only	<b>()</b>					
		Session 8: Key	note -2; Ses	sion 9-10: EUV Sources 1-2								
		<del>-</del>		/ Optics / Metrology								
	Session 8: Keynote -2; Session Chair: Bruno La Fontaine											
				Breakfast	0:30	8:00 AM	8:30 AM					
					0:10	8:30 AM	8:40 AM					
	Introduction	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements								
					0:30	8:40 AM	9:10 AM					
				The Next Step in Moore's Law: High NA								
8 P3	Keynote -2	Jan van Schoot	ASML	EUV Imaging and Overlay Performance								
					0:30	9:10 AM	9:40 AM					
				Pushing for record reflectivities for short								
8 P2	Keynote -2	Marcelo Ackermann	UTewnte	wavelength multilayers – EUV and beyond								
			University of	EUVL and Prospect for the Next Generation	0:30	9:40 AM	10:10 AM					
8 P6	Keynote -2	Takeo Watanabe	Hyogo	EUVL								
					0:20	10:10 AM	10:30 AM					
				Coffee Break								
		Soccio	on Q: FLIV Sources	-1 ; Session Chairs: TBA								
		Jessio	m 9. EUV Sources									
				Laser-plasma Acceleration: Next	0:15	10:30 AM	10:45 AM					
				Generation X-ray Light Sources for								
9 P34	Source -1	Felicie Albert	LLNL	Industrial Applications (Invited)								
				Compact Radiation Sources from Laser-	0:15	10:45 AM	11:00 AM					
				Plasma Accelerators at LBNL's BELLA Center								
9 P33	Source -1	Jeroen van Tilborg	LBL	(Invited)								
				Commercializing Laser-Wakefield	0:15	11:00 AM	11:15 AM					
0 505	C	C. A.:	T C1	Accelerator Systems and Their Applications								
9 P36	Source -1	Steve Milton	Tau Systems	(Invited)								



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
						0:15	11:15 AM	11:30 AM
					Tm:YLF lasers for driving EUV Sources			
9	P35	Source -1	Zbynek Hubka	LLNL	(Invited)			
						0:15	11:30 AM	11:45 AM
					High-average-power EUV FEL for			
9	P43	Source -1	Dinh Nguyen	Xlight	Lithography (Invited)			
						0:15	11:45 AM	12:00 PM
				Tsinghua	The Recent Process on Steady-State			
9	P38	Source -1	Zhilong Pan	University	Microbunching EUV Light Source Project			
					Coffee Break	0:20	12:00 PM	12:20 PM



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish		
	Session 10: EUV Sources -2, Session Co-Chairs: TBA									
						0:15	12:20 PM	12:35 PM		
					Modeling a Discharge-Produced Plasma					
10	P32	Source -2	Daniel Arcaro	Energetiq	(DPP) EUV Source (Invited)					
						0:15	12:35 PM	12:50 PM		
					Nanoscale Coherent Imaging and					
					Functional Characterization using Tabletop-					
10	P37	Source -2	Henry Kapteyn	K&M Labs	Scale Coherent EUV Sources (Invited)					
				Class 5	EUV and Soft-X-Ray Photonic Integrated	0:15	12:50 PM	1:05 PM		
				Photonics	Circuits (XPICs) - Overview and First Results					
10	P40	Source -2	Robert Reidel	GmbH	at 13.5 nm					
						0:15	1:05 PM	1:20 PM		
					Development Of High-Brightness Xe LPP					
10	P31	Source -2	Dong Gun Lee	E-Sol	Source And Its Applications (Invited)					
						1:00	1:20 PM	2:20 PM		
					Lunch					



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish			
	Session 11: EUV Mask / Optics /Metrology - 1; Session Chairs: TBA										
						0:15	2:20 PM	2:35 PM			
		Mask			Status and Outlook of EUV optics at ZEISS						
11	P22	/Optics/Metrology	Martin Kaumanns	Carl Zeiss	(Invited)						
						0:15	2:35 PM	2:50 PM			
		Mask			Ion Beam Deposition over Larger Form-						
11	P15	/Optics/Metrology	Katrina Rook	Veeco	Factor EUV Mask Blanks (Invited)						
					Efforts in the Development of EUV Masks	0:15	2:50 PM	3:05 PM			
		Mask			within the Context of a Merchant Mask						
11	P19	/Optics/Metrology	Hiroki Deguchi	DNP	Shop						
						0:15	3:05 PM	3:20 PM			
		Mask			Computational Lithography Solutions for						
11	P23	/Optics/Metrology	Michael Lam	Synopsys	High NA EUV with Mask Stitching (Invited)						
					Coffee Break	0:20	3:20 PM	3:40 PM			



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
			Session 12: EUV	Mask / Optics /M	letrology - 2; Session Chairs: TBA			
						0:15	3:40 PM	3:55 PM
		Mask						
12	P11	/Optics/Metrology	Stuart Sherwin	EUV Tech	EUV Tech n/k Tool			
						0:15	3:55 PM	4:10 PM
		Mask			Effects of EUV Multilayer Roughness in High			
12	P12	/Optics/Metrology	Luke Long	EUV Tech	NA EUV Lithography			
						0:15	4:10 PM	4:25 PM
		Mask			Mask-side Hyper-NA imaging on the SHARP			
12	P14	/Optics/Metrology	Marcus Benk	CXRO	EUV mask microscope			
						0:15	4:25 PM	4:40 PM
		Mask			Integrating Actinic EUV Research with			
12	P18	/Optics/Metrology	Sangsul Lee	POSTECH	Advanced Analytical Technologies (Invited)			
						0:10	4:40 PM	4:50 PM
			Vivek Bakshi	EUV Litho, Inc.	Announcements			
			Workshop Adio	urned. Leave f	for Off-Site Workshop Dinner			



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